

REMARKS

Examination on the merits is respectfully requested. No claims having been deleted or added, the Applicants respectfully submit that claims 1-18 are properly under consideration in the present application.

Claim 7 has been amended to remove extraneous text from the claim that was not intended to be a part of the instant application. Applicants further submit a substitute specification for the Examiner's consideration and convenience.

If any points remain in issue which the Examiner feels may be best resolved through a personal or telephone interview, he is kindly requested to contact the undersigned at the telephone number listed below.

Attached hereto is a marked-up version of the changes made to the specification and claims by the current amendment. The attached Appendix is captioned **"Version with markings to show changes made"**.

Respectfully submitted,

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Enclosure: Appendix



APPENDIX

VERSION WITH MARKINGS TO SHOW CHANGES MADE

IN THE CLAIMS:

7. (Amended) A method for forming a multi-transmittance photomask on a transparent substrate according to claim 5, further comprising the step of forming an etch barrier layer on the second light blocking layer before forming the third light blocking layer.

[[?It seems that without some interlayer film it would be difficult to control the removal of the third chromium layer from the second chromium layer. And if the control is good, could a selective partial etch of a thick second chromium layer dispense with the need for a third layer? Please advise?]]

- END OF APPENDIX -

